

ABSTRACT OF THE DISCLOSURE

A method for making a dry plating built-up film
5 comprises providing silicon carbide as a starting source
and subjecting to dry plating while changing a
concentration of a reactive gas continuously or
intermittently to deposit and form, on a substrate, a thin
film having different refractive indices along its
10 thickness. A method for making a sputter built-up film is
also described, which comprising providing silicon carbide
as a target and subjecting to sputtering while changing
making electric power against the target continuously or
intermittently to deposit and form a thin film having
15 different refractive indices along its thickness.